## UNITED STATES PATENT AND TRADEMARK OFFICE **CERTIFICATE OF CORRECTION**

Page 1 of 2

PATENT NO. : 6,833,294 B1 DATED

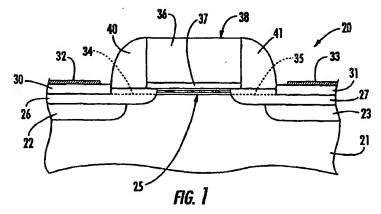
: December 21, 2004

INVENTOR(S) : Mears et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

#### Drawings,

Delete FIG. 1 and insert new FIG. 1



## Column 1,

Line 43, delete "on a binary" insert -- on binary --

Line 67, delete "in a silicon" insert -- in silicon --

#### Column 2,

Line 1, delete "electromuminescence" insert -- electroluminescence --

Line 23, delete "Published-Great" insert -- Published Great --

Line 60, delete "superlattice and has" insert -- superlattice has --

## Column 4,

Line 18, delete "tensor"," insert -- tensor, --

#### Column 5,

Lines 11 and 60, delete "gate 35" insert -- gate 38 --

#### Column 7,

Line 63, delete "from the both" insert -- from both --

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It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

#### Column 9,

Lines 44-46, delete "In other processes and devices the structures of the present invention may be formed on a portion of a wafer or across substantially all of a wafer."

Line 59, delete "also formed" insert -- also be formed --

Signed and Sealed this

Nineteenth Day of July, 2005

JON W. DUDAS
Director of the United States Patent and Trademark Office